

Micro-Stereolithography: Physics and Technologies

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ONR Young Investigator Award

Outline

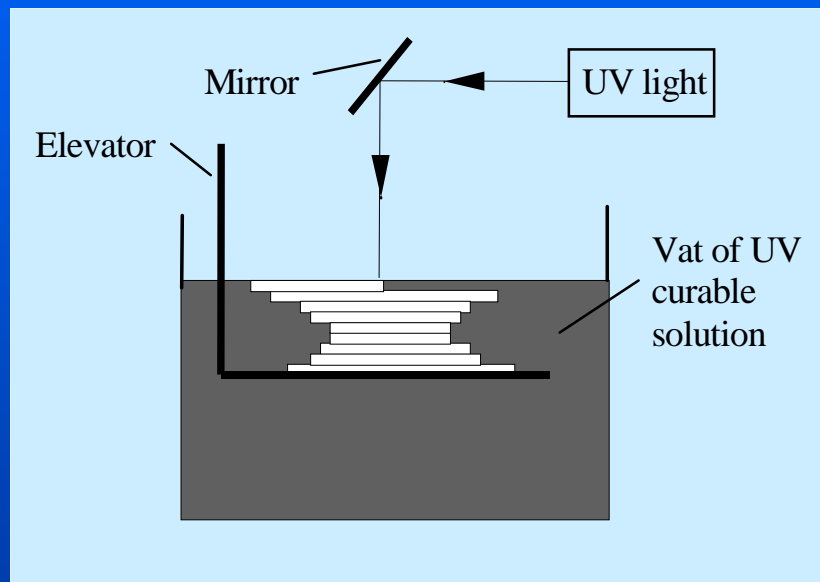
- Introduction
- Micro-Stereolithography (μ SL)
 - μ SL principles and apparatus design
 - Prototyping of polymeric and ceramic microstructures
 - Experiment and modeling
- Applications

Background

- Future high Performance MEMS requires:
 - 3D complex micro-structures
 - Incorporating with a broader spectrum of materials (Smart materials, functional polymer, and magnetic alloys)
- However, current silicon IC fabrication can not provide an effective solution.
- Other efforts:
 - X-ray LIGA: high aspect ratio 2.5D, but not true 3D
 - Micro-mechanical machining: complex 3D, but very slow and severe tool wear
 - EFAB, 3D, need many masks needed and limited to metal

A New Approach— Scale Down Rapid Prototyping Technologies

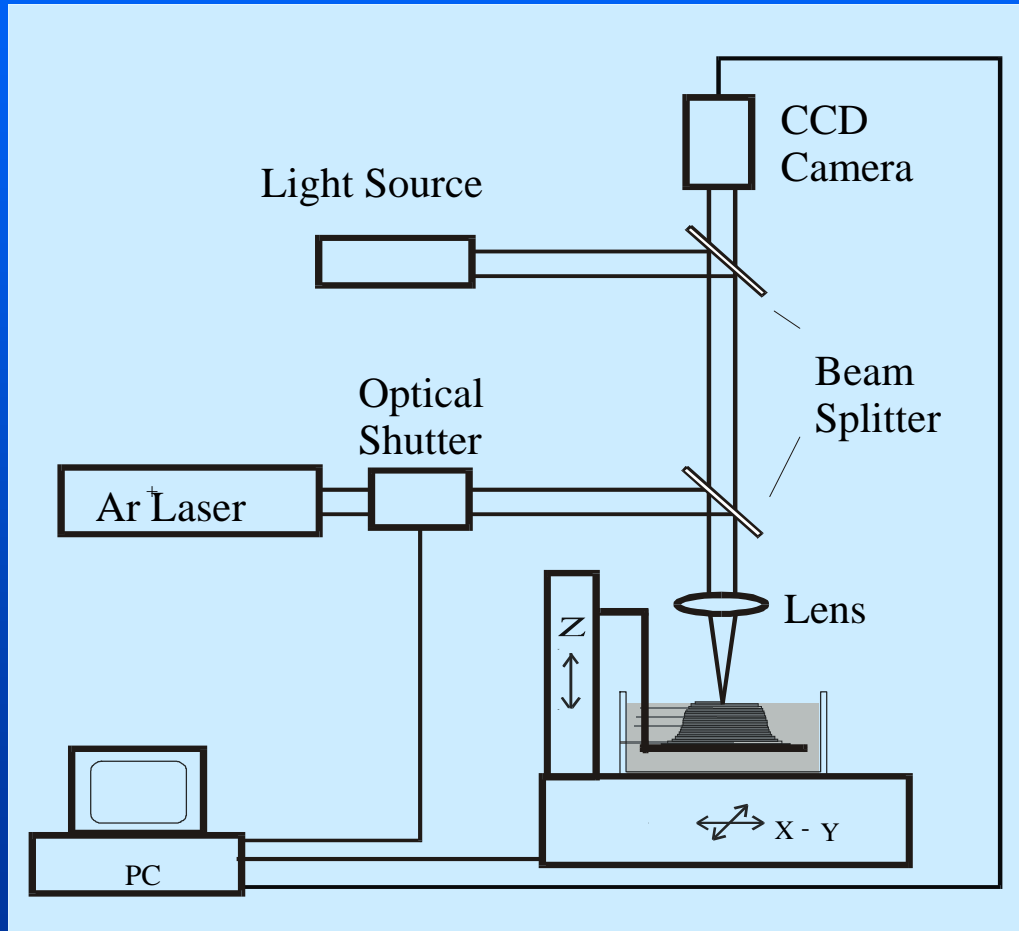
Micro-Stereolithography



(Ikuta, 1996)

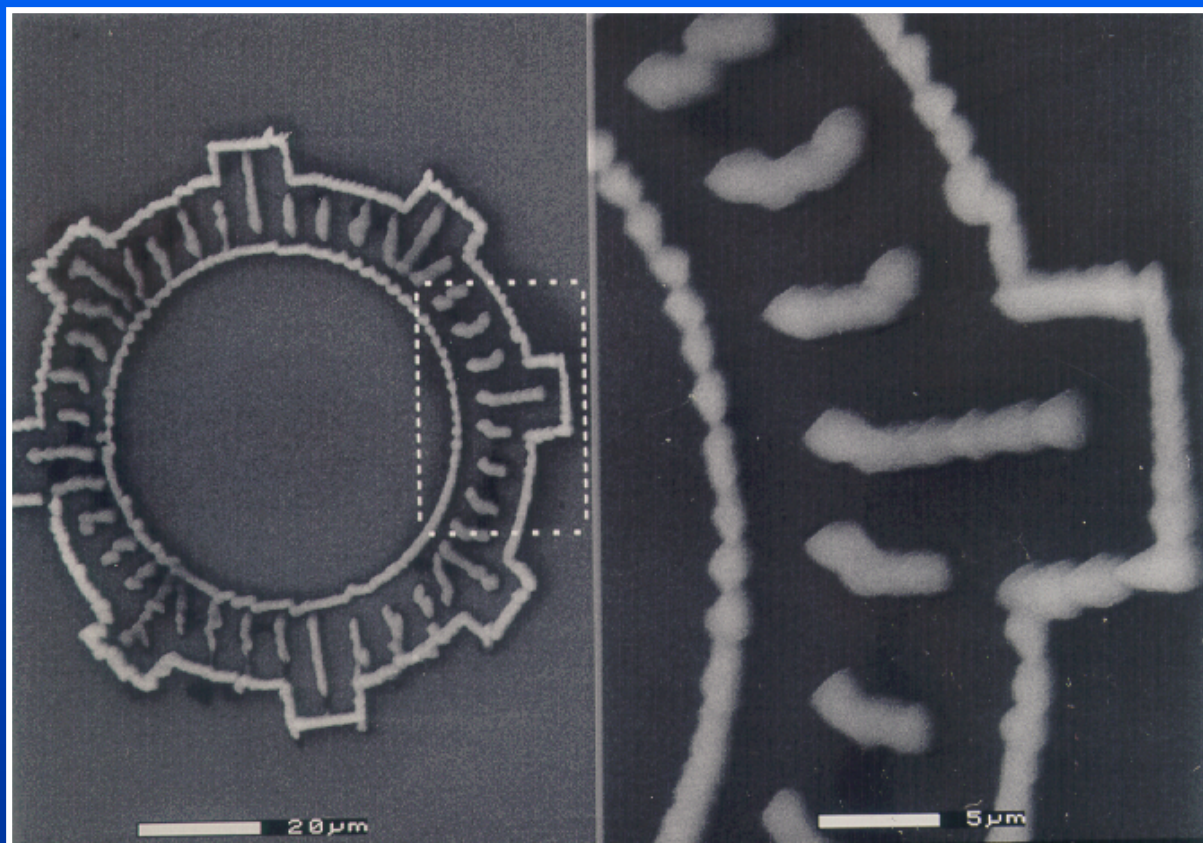
- UV laser micro photo-forming of 3D complex micro-parts
- A layer-by-layer additive process
- CAD design capability
- Incorporation of many functional materials

An Advanced Micro-Stereolithography Apparatus



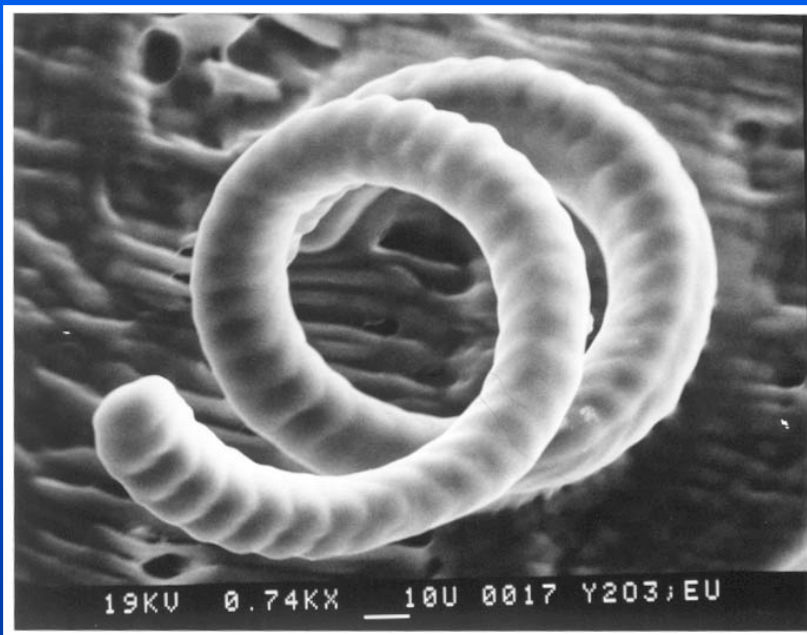
- Laser: $\lambda=364$ nm
- X-Y-Z stepper resolution: $0.5\ \mu\text{m}$
- UV beam spot: $1\ \mu\text{m}$

Test Pattern with 2 μm Line Width

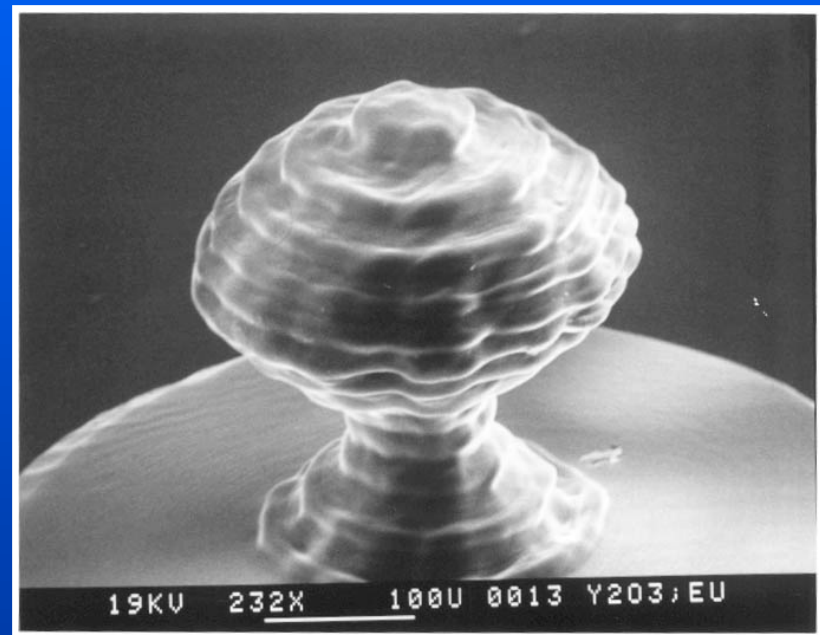


Micro-Stereolithography of 3D Complex Structures

- Micro-spring

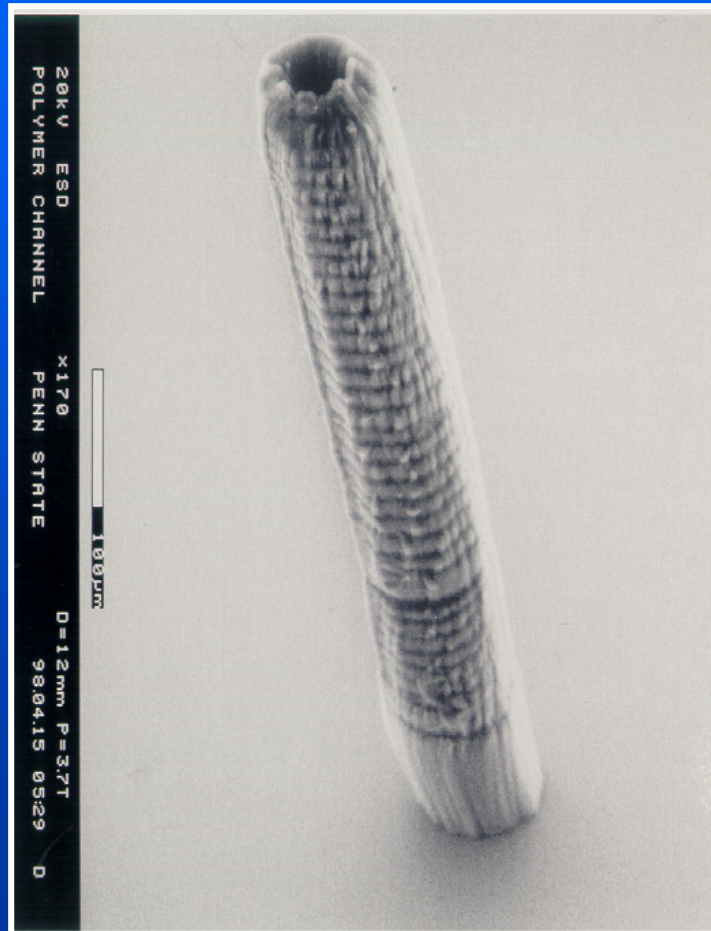


- Micro-mushroom



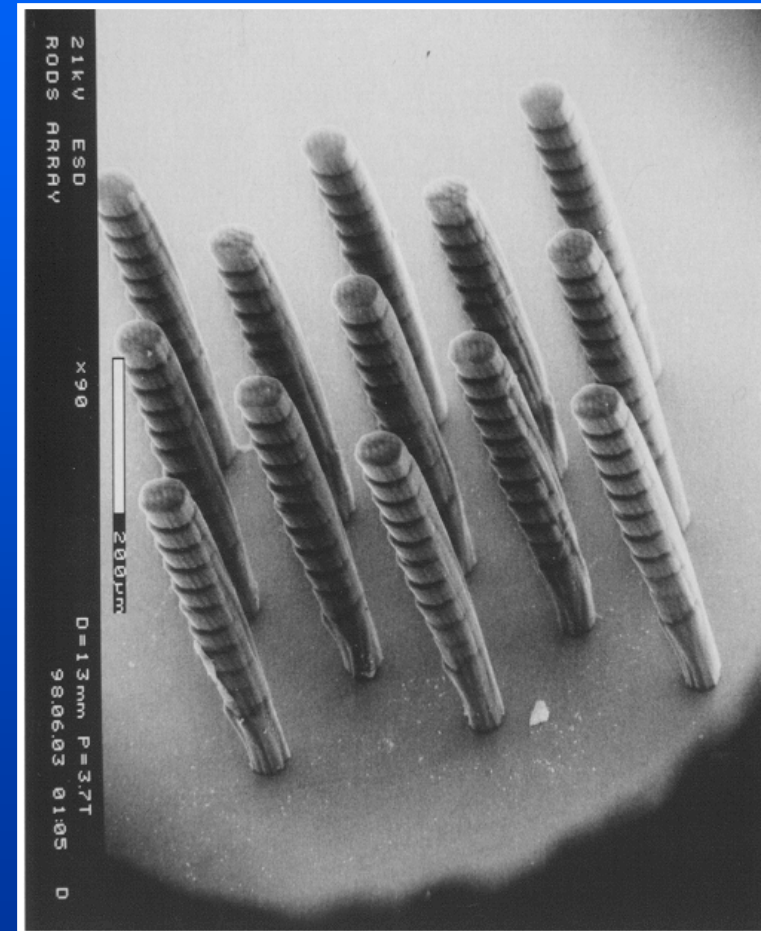
- **Micro-tube**

(50 μm inner diameter and 800 μm long)



- **Micro-rod Array**

(50 μm diameter and 500 μm long)



Simulation of Micro-Stereolithography of Polymer

Photopolymerization

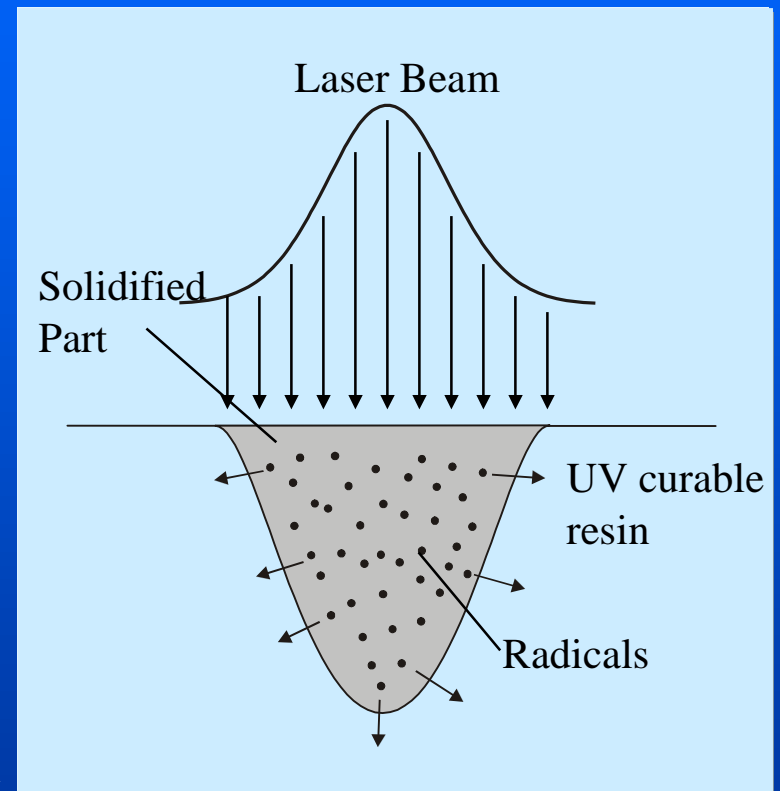
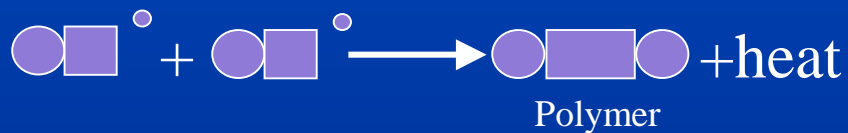
- **Initiation:**



- **Propagation:**



- **Termination:**



Simulation Approach

- **Light absorption:**

$$\frac{dI}{dz} = -\epsilon [S] I$$

- **Photoinitiation:**

$$\frac{d[S]}{dt} = -\psi\epsilon [S] I$$

- **Diffusion of Radicals:**

$$\frac{d[R]}{dt} = D \left[\frac{1}{r} \frac{\partial}{\partial r} \left(r \frac{\partial [R]}{\partial r} \right) + \frac{\partial^2 [R]}{\partial z^2} \right] + \phi\epsilon [S] I - k_t [R]^2$$

- **Polymerization Kinetics:**

$$\frac{d[M]}{dt} = -k_p [R][M]$$

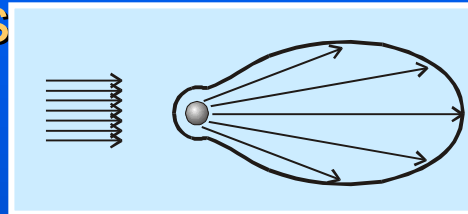
- **Heat Transfer:**

$$\rho C_p \frac{\partial T}{\partial t} = k \left[\frac{1}{r} \frac{\partial}{\partial r} \left(r \frac{\partial T}{\partial r} \right) + \frac{\partial^2 T}{\partial z^2} \right] - k_p [R][M] \Delta H$$

Monte-Carlo Simulation of μ SL of Ceramics

Single photon tracing processes

- Scattering
 - Mie theory

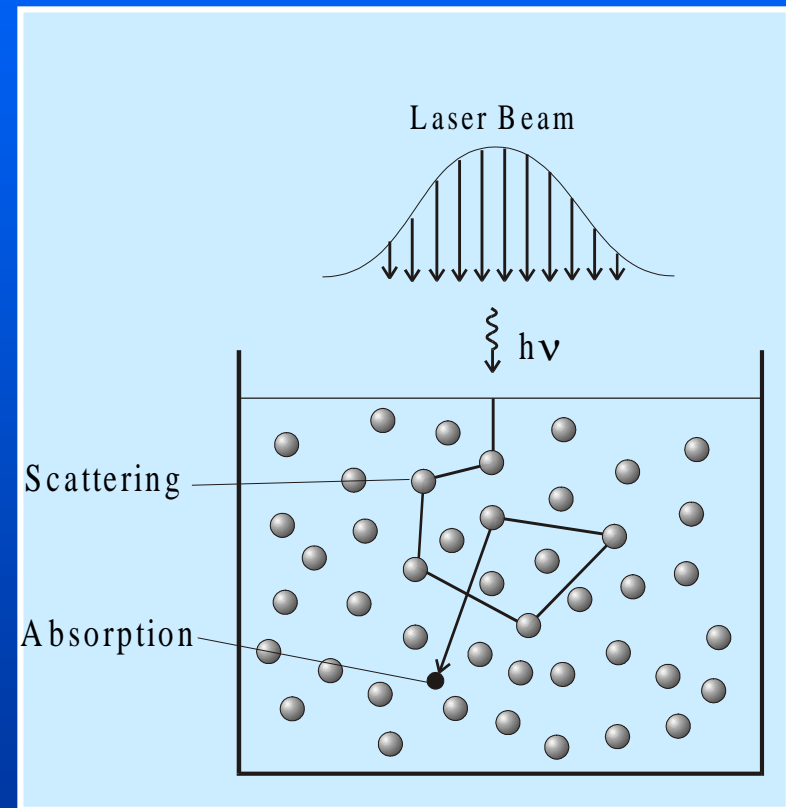


- Absorption during traveling
 - travel:
 - absorption:

$$P = e^{-l/\lambda}, \lambda = \frac{4 \cdot r}{3 \cdot s} \text{ (MFP)}$$

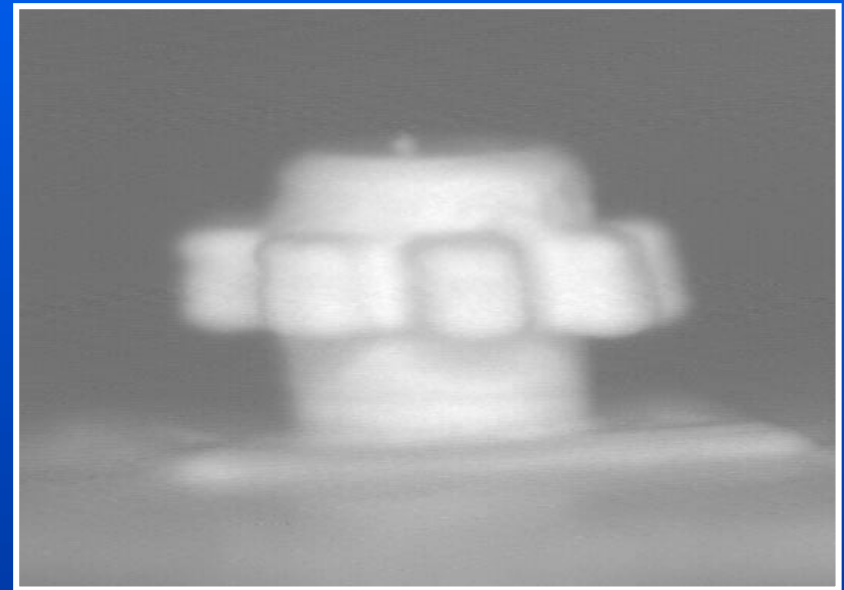
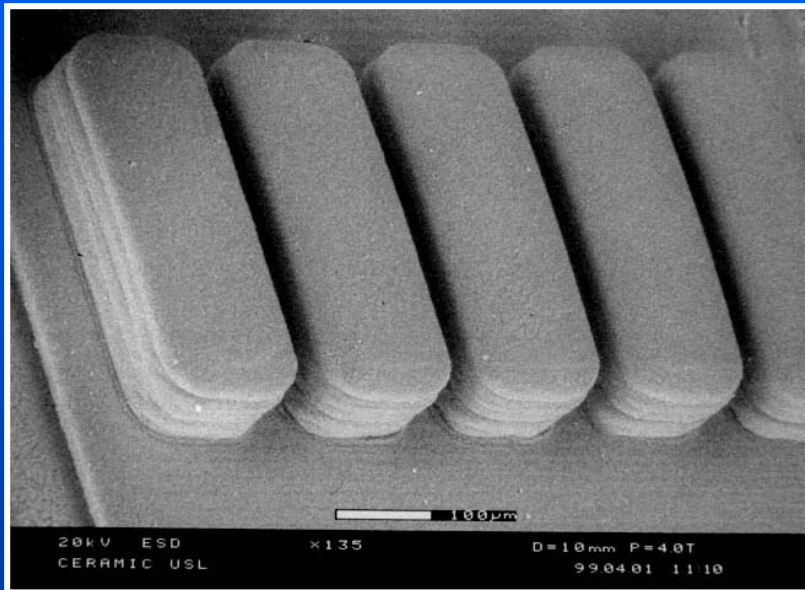
$$P_a = e^{-\epsilon \cdot l}$$

- Photo polymerization



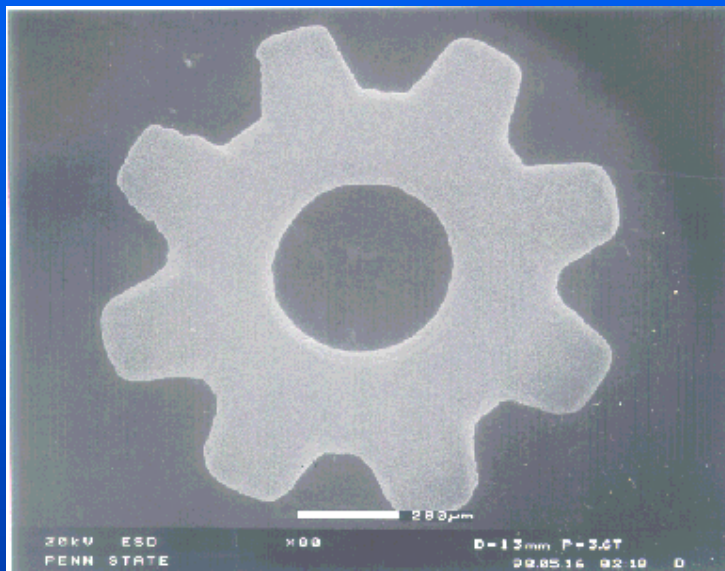
3D Ceramic μ SL

30 μ m Alumina Micro Channels 400 μ m Alumina Micro Gear

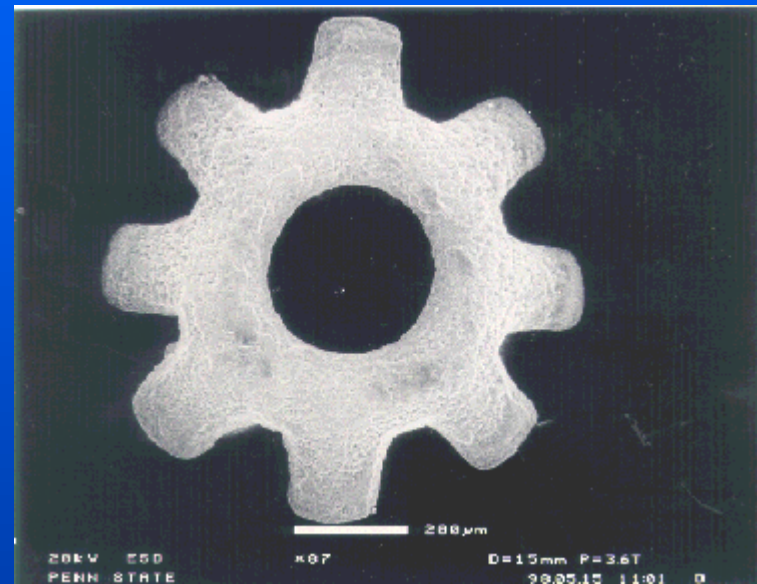


Micro-Stereolithography of Ceramic Structures

- Green Alumina Gear

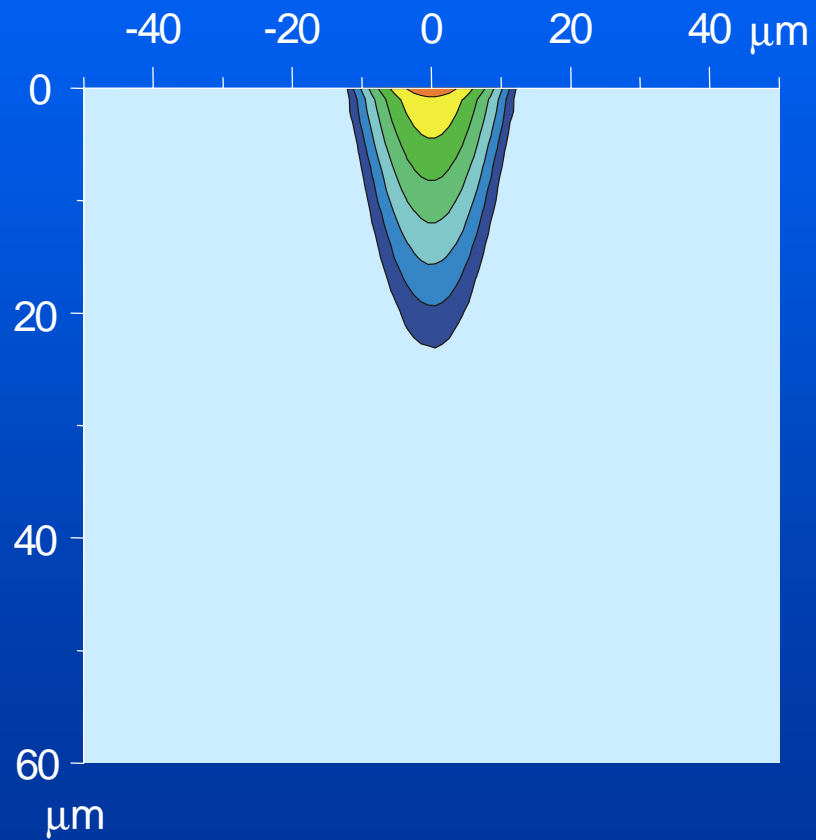


- Sintered Alumina Gear

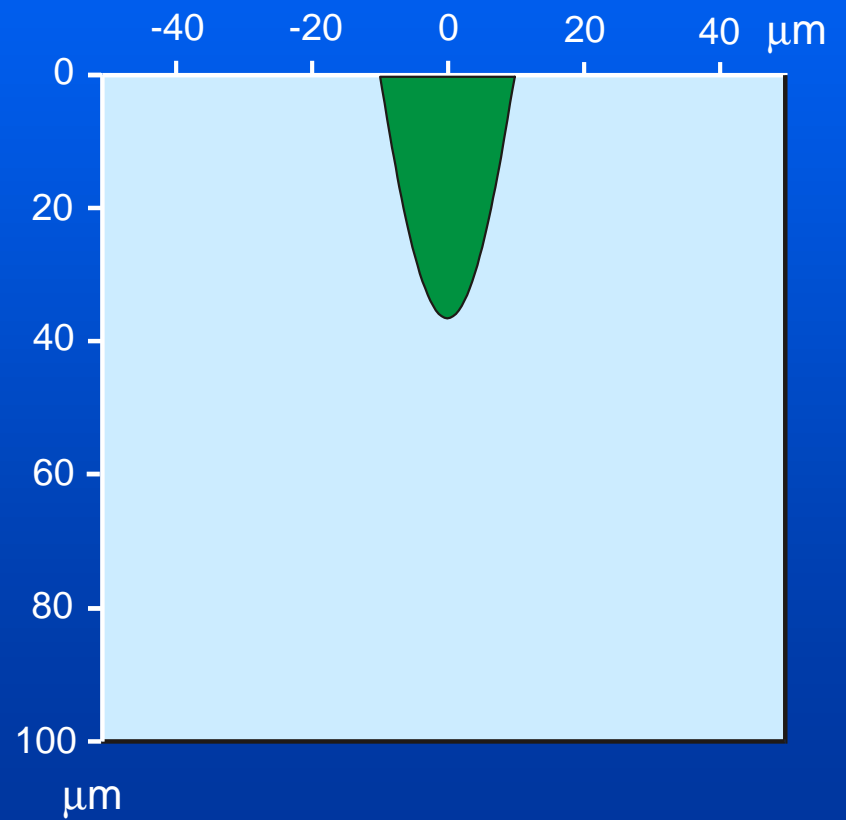


Sintered at 1400 °C and 3 hours
Shrinkage due to sintering: 5-16%

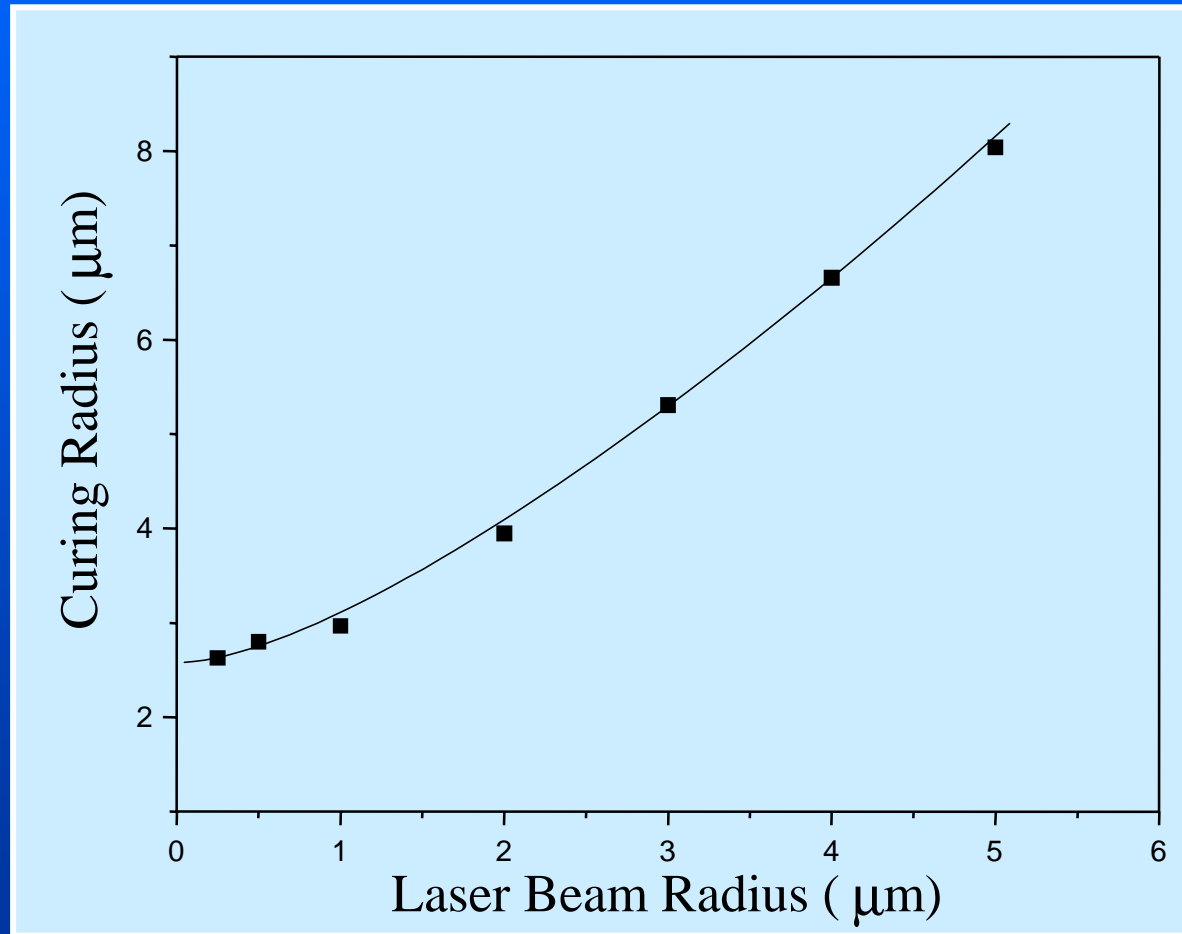
Light Scattering



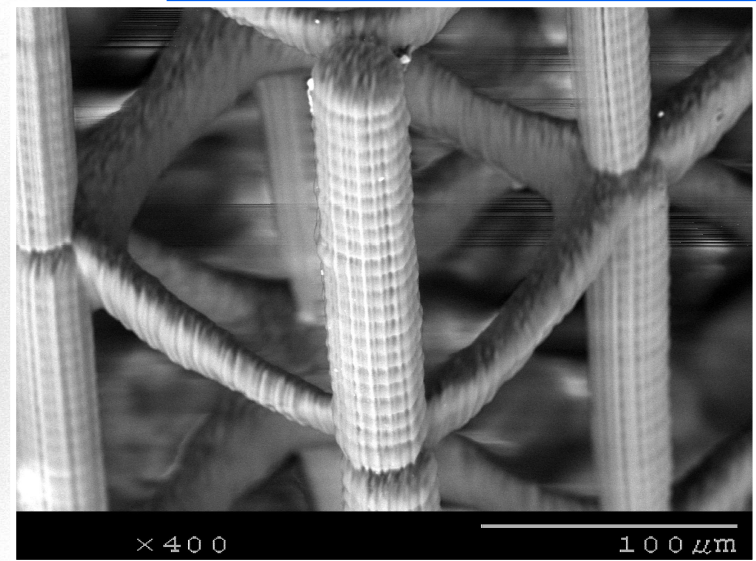
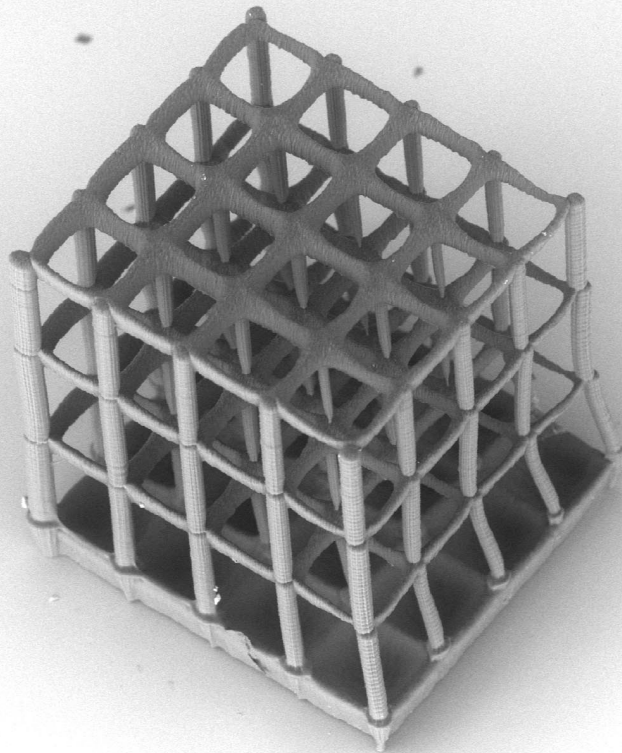
Polymerization



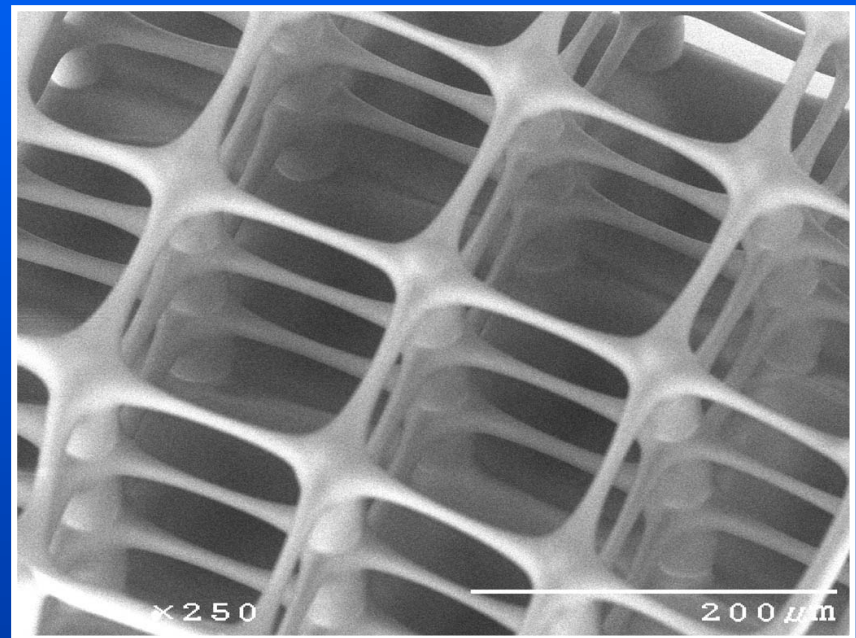
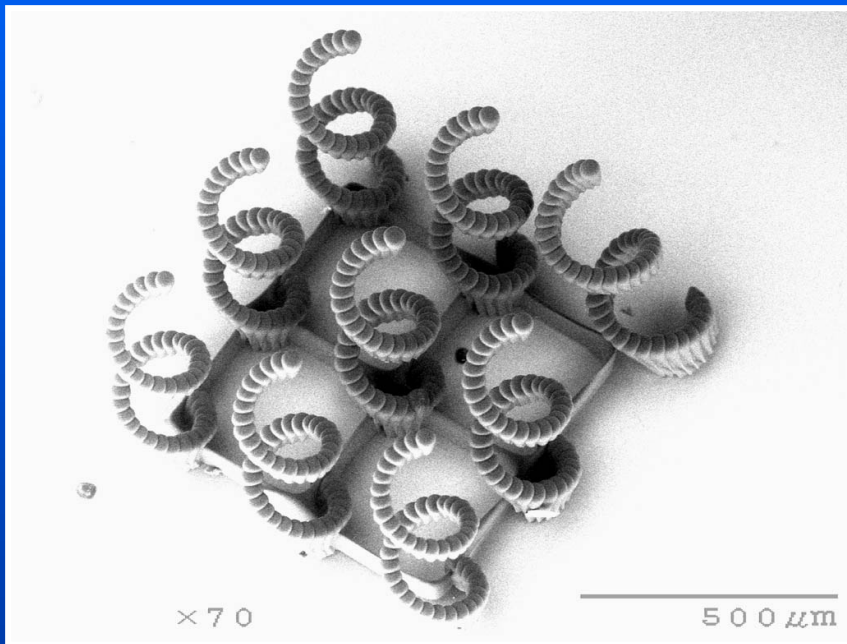
Lateral Resolution Limit in μ SL of Ceramics

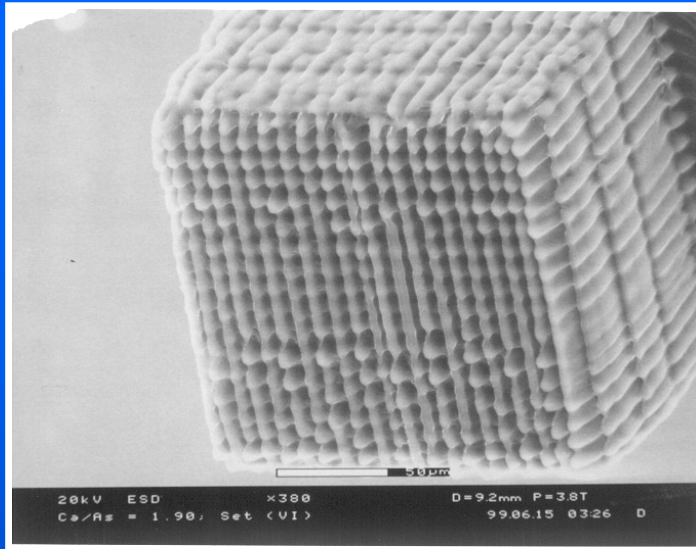


3D Matrix by DMD- μ SL

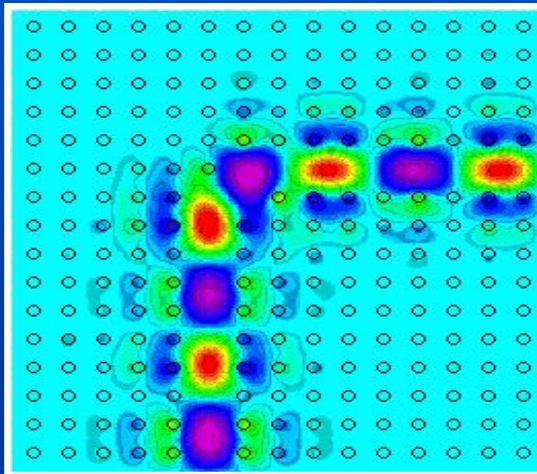


3D Coils Array and Micro-Matrix





(Zhang, 1999)



(Joannopoulos, 1996)

3D Photonic Band-gap Crystals

- Transmit/forbid light beam of selected wavelength (12 dB)
- Defects are pre-designed by CAD and embedded into the PBG by micro-stereolithography (decide what type defects and where they located, which is impossible in atomic scale defects in semiconductor)

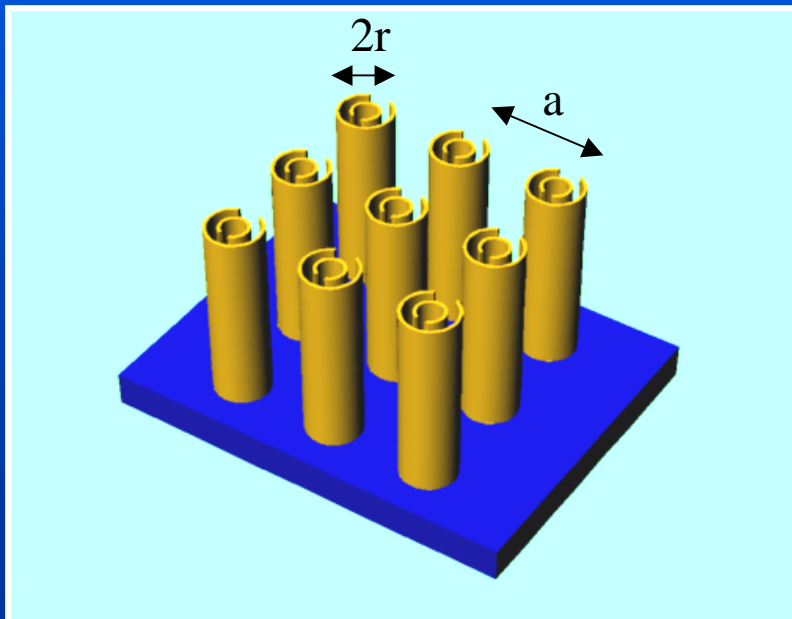
Applications

- Loss-free optical fiber
- High efficiency visible –IR bandpass filter/waveguide
- Resonant cavity in solid state laser

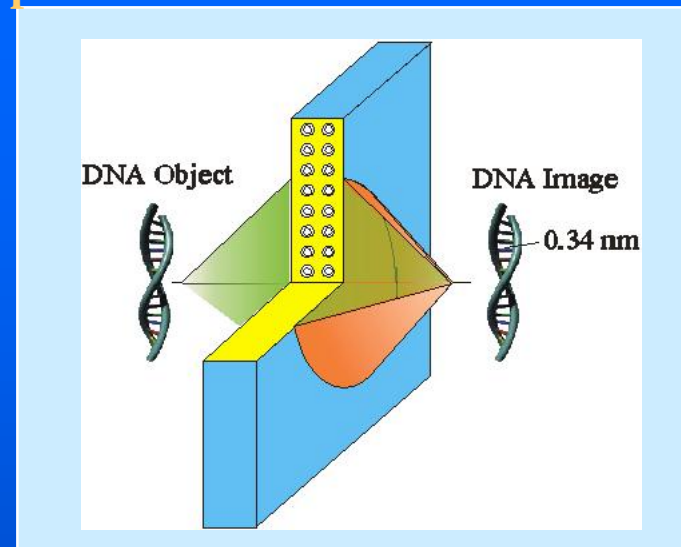
Artificial Materials With Unprecedented Properties

(Theoretical work of John Pendry, 2000)

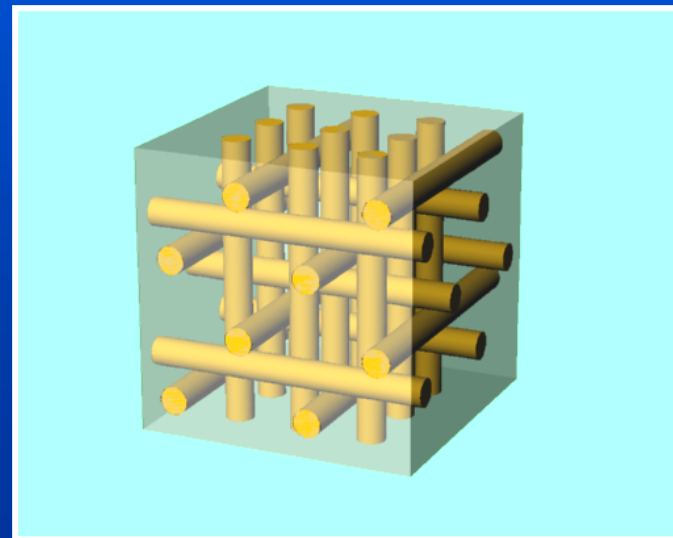
Artificial Magnetism at High f



Super-lens

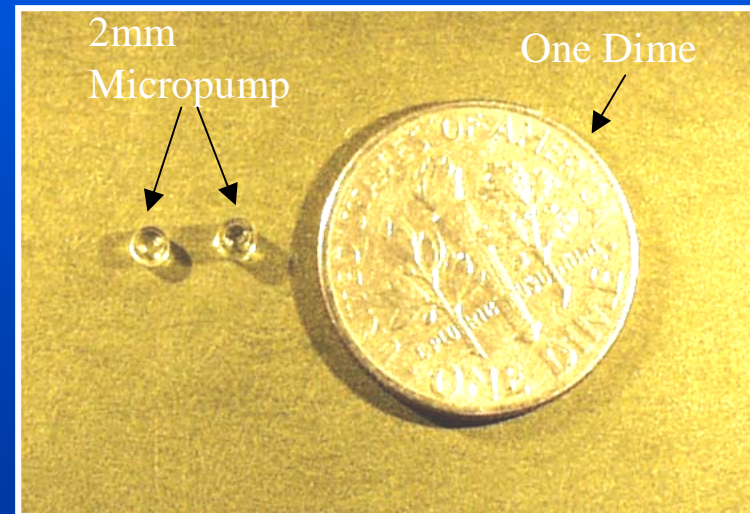
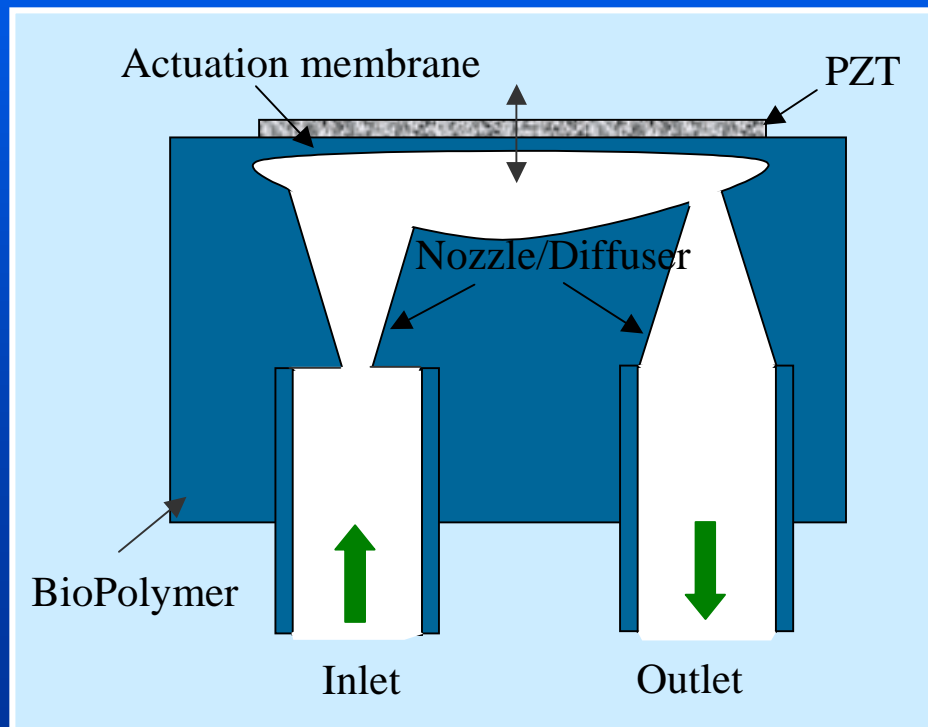


Artificial Plasma



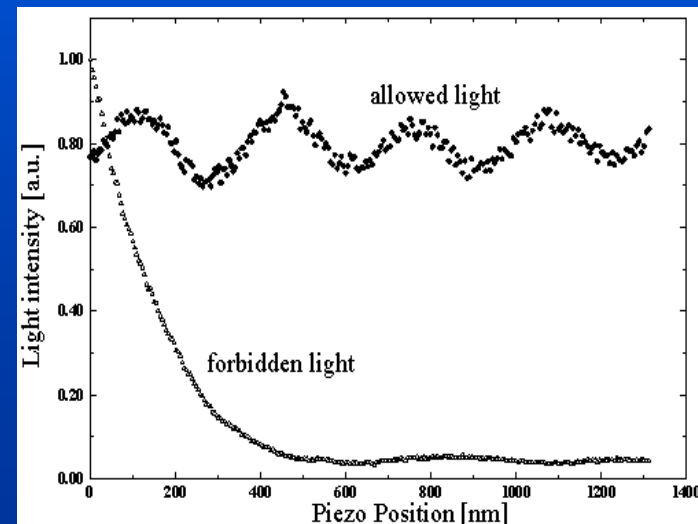
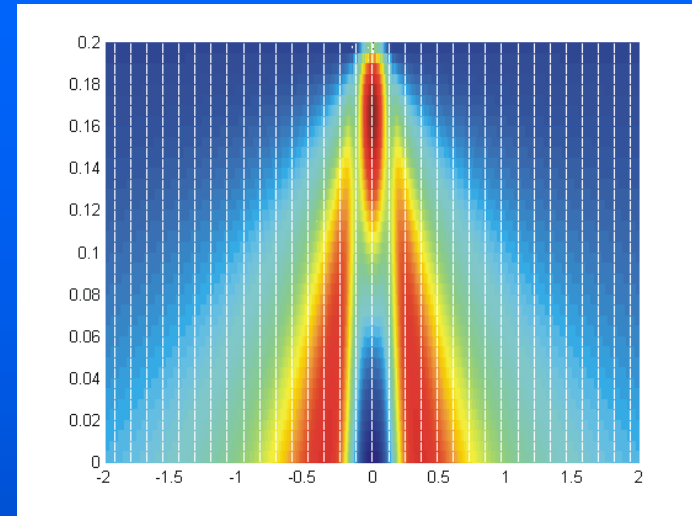
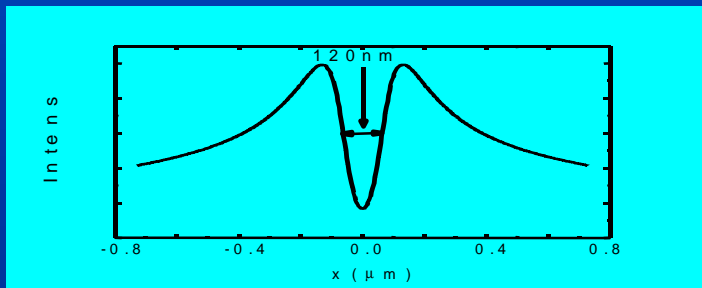
3D Valveless Micropump

- Truly 3D cavity structure to optimize the design
- High reliability due to no movable valves
- A wide variety of materials (eg. Bio-polymer)



Near Field Optical nanolithography(NSOL)

- Near field scanning optical microscopy (NSOM)- a proven technology to break the diffraction limit.
- 2D nanopatterning with NSOM demonstrated features with $\sim 100\text{nm}$ lateral resolution
- Computer simulation propose that NSOM has the potential in 3D nanolithography



Conclusions

- Scanning micro-stereolithography has been developed
- Micro-stereolithography of complex 3D micro-structures has been demonstrated; For the first time, μ SL of ceramic micro-structures has been succeeded
- Theoretical Simulation of micro-stereolithography shows good agreements with preliminary experimental results
- The unique 3D techniques enable exciting applications in photonics, bioMEMS and possibly novel thermally engineered materials.